

Applicants: Jai-Moo YOO et al.
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Amendments to the Claims:

1. (Currently amended) A method for manufacturing a biaxially textured metal material comprising the steps of,
manufacturing a plating solution comprising 100~400 g/l nickel sulfate, 70 g/l or less nickel chloride, 20~80 g/l boric acid, 50 g/l or less sodium sulfate, 10 g/l or less sodium tungstate and 10 g/l or less cobalt chloride at pH 2~4 and 50~80°C;

depositing a biaxially textured metal layer by an electroplating process in ~~a~~ the ~~plating solution comprising 100~400 g/l nickel sulfate, 0~70 g/l nickel chloride, 20~80 g/l boric acid, 0~50 g/l sodium sulfate, 0~10 g/l sodium tungstate and 0~10 g/l cobalt chloride at pH 2~4 and 50~80°C~~ on the surface of a ~~metal substrate~~ rotating cylindrical cathode having a single-crystalline or a quasi-single-crystalline orientation; and

peeling the deposited biaxially textured metal layer off the ~~metal substrate~~ rotating cylindrical cathode after electroplating wherein the peeled biaxially textured metal layer has substantially the same texture orientation as that of the metal substrate.

2. (Canceled)

3. (Currently amended) The method for manufacturing a biaxially textured metal material according to claim 1, wherein the electroplating process is a direct current electroplating

process (DC process) in which the biaxially textured metal layer is deposited in ~~a~~the plating solution at a cathode current density of 3~20 A/dm² ~~using a direct current electroplating process (DC process),~~ and the deposited metal layer ~~having~~has a texture fraction (TF) of 0.97 or more on the (001) plane.

4. (Currently amended) The method for manufacturing a biaxially textured metal material according to claim 1, wherein the electroplating process is a pulse current electroplating process (PC process) in which the biaxially textured metal layer is deposited in ~~a~~the plating solution under conditions of a cathode current density of 3~20 A/dm², a cathode current time of 1~100 msec and a down time of 1~100 msec ~~using a pulse current electroplating process (PC process),~~ and the deposited metal layer ~~having~~has a texture fraction (TF) of 0.97 or more on the (001) plane.

5. (Currently amended) The method for manufacturing a biaxially textured metal material according to claim 1, wherein the electroplating process is a periodic reverse current electroplating process (PR process) in which the biaxially textured metal layer is deposited in ~~a~~the plating solution under conditions of a cathode current density of 3~20 A/dm², a cathode current time of 1~100 msec and an anode current time of 1~100 msec ~~using a periodic reverse current plating process (PR process),~~ and the deposited metal layer ~~having~~has a texture fraction (TF) of 0.97 or more on the (001) plane.

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6. (Canceled)

7. (Canceled)

8. (Canceled)